

J.G. Martin et al.: "Mechanisms of silicone dioxide deposition from the low pressure chemical vapor deposition of diethylsilane/oxygen mixtures", Journal of the Electrochemical Society, Vol. 142, November 1995, No. 11, pp. 3873-3880, INSPEC Abstract;

International Search Report dated July 2, 2002.

In accordance with 37 C.F.R. 1.97(e) the undersigned herewith states that each item of information contained in the information disclosure statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the information disclosure statement.

In accordance with 37 C.F.R. 1.97 (c) (1), consideration of this Information Disclosure Statement is requested.

Respectfully submitted,

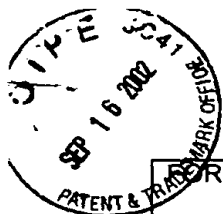

For Applicant

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FORM PTO-1449 (SUBSTITUTE)				Attorney Docket No.: Z&PINFP10306		Applic. No. 10/034,053	
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				Applicant Annette Snger			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))				Filing Date December 20, 2001		Group Art Unit 1763	
U.S. PATENT DOCUMENTS							
EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
	A	3,334,103	08/01/67	Feldman et al.			
	B	5,589,425	12/31/96	Hoshino et al.			
	C	5,637,351	06/10/97	O'Neal et al.			
	D						
	E						
	F						
	G						
	H						
	I						
FOREIGN PATENT DOCUMENT							
		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES NO
	J	1 108 468 A1	06/20/01	Europe			X
	K	1 158 070 A1	11/28/01	Europe			X
	L						
	M						
	N						
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
	O	J.G. Martin et al.: "Mechanisms of silicone dioxide deposition from the low pressure chemical vapor deposition of diethylsilane/oxygen mixtures", Journal of the Electrochemical Society, Vol. 142, November 1995, No. 11, pp. 3873-3880, INSPEC Abstract					
	P						
EXAMINER				DATE CONSIDERED			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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